



제 31회 한국반도체학술대회

The 31st Korean Conference on Semiconductors

2024년 1월 24일(수)-26일(금) | 경주화백컨벤션센터(HICO)

2024년 1월 25일(목), 15:30-17:15

Room A(101), 1층

B. Patterning (Lithography & Etch Technology) 분과

[TA3-B] Advanced Plasma Etching II

좌장: 채희엽 교수(성균관대학교)

초청발표 TA3-B-1 15:30-16:00	나노식각 공정진단·제어기술 Real-Time PI-VM 소개 김곤호 ^{1,2} ¹ 서울대학교 원자핵공학과, ² 서울대학교 플라즈마 응용연구실
TA3-B-2 16:00-16:15	OLED 디스플레이 제조를 위한 다중 금속막 식각 공정의 PI-VM 기반 패턴 제어 박윤아 ¹ , 노연길 ¹ , 서라벌 ¹ , 송봉섭 ¹ , 김곤호 ² , 박설혜 ¹ ¹ 삼성디스플레이, ² 서울대학교
TA3-B-3 16:15-16:30	Enhancement of Plasma Uniformity in Adaptive Dry Etcher with Convex-Shaped Electrodes Sanghyun Kang ¹ , Seokchan Yoon ² , Jaehyuk Lim ¹ , and Changhwan Shin ² ¹ Department of Electrical and Computer Engineering, Sungkyunkwan University, ² School of Electrical Engineering, Korea University
TA3-B-4 16:30-16:45	Observation of the Floating Sheath Distribution Adjacent to a DC-biased Metal Substrate NamJae Bae ¹ , Nam-Kyun Kim ² , Haneul Lee ¹ , Yunchang Jang ² , Seolhye Park ³ , and Gon-Ho Kim ¹ ¹ Seoul University, ² Samsung Electronics Co., Ltd., ³ Samsung Display Co., Ltd.
TA3-B-5 16:45-17:00	Nickel-silicide Alloy as an Alternative to Noble Metal Catalyst for Metal-assisted Chemical Etching of Si Haekyun Bong, Kyunghwan Kim, Sunhae Choi, and Jungwoo Oh School of Integrated Technology, Yonsei University
TA3-B-6 17:00-17:15	Correlation with the Microstructure and Synergistic Physiochemical Etching Resistance of Nanocomposites under CF ₄ /Ar/O ₂ Plasma Conditions in Plasma Etching Chamber Ho Jin Ma ¹ , Mi-Ju Kim ¹ , Ha-Neul Kim ¹ , Jae-Woong Ko ¹ , Jae-Wook Lee ¹ , Hyo-Chang Lee ² , and Young-Jo Park ¹ ¹ KIMS, ² Korea Aerospace University